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12-20-02
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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

TECHNOLOGY CENTER 2003

In re the Application of

Kazuya OTA et al.

Group Art Unit: 2851

Application No.: 09/846,304 /

Examiner: K. Brown

Filed: May 2, 2001 /

Docket No.: 104313.01

For: APPARATUS AND METHOD FOR PATTERN EXPOSURE AND METHOD FOR
ADJUSTING THE APPARATUS

AMENDMENT UNDER 37 C.F.R. §1.111

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the June 17, 2002, Office Action, the period for response being extended
by the attached Petition for Extension of Time, please amend the above-identified application
as follows:

IN THE CLAIMS:

Please replace claim 12 as follows:

12. (Twice Amended) An exposure apparatus which exposes an object with
exposure light, comprising:

a light source in which optical components are installed and which generates
said exposure light and non-exposure light having a wavelength which is different from that
of said exposure light and including at least one of ultraviolet light and visible light;

an optical system disposed on an optical path through which said exposure
light passes and including at least an illumination system which irradiates said exposure light
onto an original;

a first sensor that receives said non-exposure light from said light source
through at least a part of said optical system and output of which is used in adjustment of an

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